

SHEET 1 OF 9

| INFORMATION DISCLOSURE CITATION PTO-1449 | | ATTY. DOCKET NO. 14912.786 | | SERIAL NO. 10/053,138 | | | |
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| | | APPLICANT Stephen E. Savas | | | | | |
| | | FILING DATE 01/18/2002 | | GROUP 1763 | | | |
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| pt | 5,556,521 | 09/1996 | Ghanbari | 204 | 192.37 | | |
| pt | 5,449,432 | 09/1995 | Hanaw | 156 | 643.1 | | |
| pt | 5,696,428 | 12/1997 | Pasch | 315 | 111.21 | | |
| pt | 5,690,781 | 11/1997 | Yoshida et al. | 156 | 345 | | |
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| EXAMINER'S INITIALS | PATENT NO. | DATE | COUNTRY | CLASS | SUBCLASS | TRANSLATION | |
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| pt | 2 105 729 A | 30.03.83 | Great Britain | C08 J7/00 | C08F 2/52 | <input type="checkbox"/> | <input checked="" type="checkbox"/> |
| pt | 408288272 | 11/1996 | Japan | C23C | 16/50 | <input type="checkbox"/> | <input type="checkbox"/> |
| pt | 0154482A2 | 11/1985 | Europe | C23C | 16/00 | <input type="checkbox"/> | <input type="checkbox"/> |
| pt | 2240114A | 07/1991 | Great Britain | C23C | 16/26 | <input checked="" type="checkbox"/> | <input type="checkbox"/> |
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| pk | 5,419,805 | 05/30/1995 | Jolly | 156 | 643.1 | 02/18/1994 | |
| pk | 5,399,237 | 03/21/1995 | Keswick et al. | 156 | 643 | 01/27/1994 | |
| pk | 5,362,358 | 11/08/1994 | Yamagata et al. | 156 | 643 | 05/14/1993 | |
| pk | 5,354,417 | 10/11/1994 | Cheung et al. | 156 | 643 | 10/13/1993 | |
| pk | 5,354,381 | 10/11/1994 | Sheng | 118 | 723 | 05/07/1993 | |
| pk | 5,344,792 | 09/06/1994 | Sandhu et al. | 437 | 200 | 03/04/1993 | |
| pk | 5,332,441 | 07/26/1994 | Barnes et al. | 118 | 723 | 10/31/1991 | |
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| pk | 5,289,010 | 02/22/1994 | Shohet | 250 | 492.21 | 12/08/1992 | |
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| FOREIGN PATENT DOCUMENTS | | | | | | | |
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| EXAMINER <i>pk Hassanzadeh</i> | | | DATE CONSIDERED <i>5-25-03</i> | | | | |

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| pt | 5,231,057 | 07/27/1993 | Doki et al. | 437 | 225 | 08/20/1991 | |
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| pt | 5,188,704 | 02/23/1993 | Babie et al. | 156 | 643 | 05/09/1991 | |
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| pl | 5,108,542 | 04/28/1992 | Lin | 156 | 643 | 08/23/1990 | |
| pl | 5,007,982 | 04/16/1991 | Tsou | 156 | 643 | 07/11/1988 | |
| pl | 4,994,715 | 02/19/1991 | Asmus et al. | 315 | 111.71 | 07/21/1988 | |
| pl | 4,933,300 | 06/12/1990 | Koinuma et al. | 437 | 110 | 02/12/1988 | |
| pl | 4,985,112 | 01/15/1991 | Egitto et al. | 156 | 643 | 02/09/1987 | |
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| pl | 4,935,661 | 06/19/1990 | Heinecke et al. | 313 | 231.31 | 06/26/1986 | |
| FOREIGN PATENT DOCUMENTS | | | | | | | |
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| ph | 4,897,365 | 01/30/1990 | Baldi et al. | 437 | 69 | 11/23/1987 | |
| ph | 4,891,118 | 01/02/1990 | Ooiwa et al. | 204 | 298 | 11/23/1988 | |
| ph | 4,863,549 | 09/05/1989 | Grünwald | 156 | 345 | 07/01/1988 | |
| ph | 4,857,140 | 08/15/1989 | Loewenstein | 156 | 643 | 03/31/1988 | |
| ph | 4,836,887 | 06/06/1989 | Daubenspeck et al. | 156 | 643 | 11/23/1987 | |
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| ph | 4,824,690 | 04/25/1989 | Heinecke et al. | 427 | 38 | 11/03/1987 | |
| ph | 4,807,016 | 02/21/1989 | Douglas | 357 | 67 | 11/20/1987 | |
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| pt | 4,734,157 | 03/29/1988 | Carbaugh et al. | 156 | 643 | 03/18/1987 | |
| pt | 4,717,447 | 01/05/1988 | Dieleman et al. | 156 | 643 | 10/31/1983 | |
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| pk | 4,075,583 | 02/21/1978 | Kershaw | 333 | 73 R | 05/24/1976 | |
| pk | 3,940,506 | 02/24/1976 | Heinecke | 427 | 38 | 05/03/1974 | |
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| pk | 4,412,119 | 10/25/1983 | Komatsu et al. | 219 | 121 PF | 05/05/1981 | |
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| pk | H. Sugai et al., "Diagnostics and control of radicals in an inductively coupled etching reactor," J. Vac. Sci. Technol. A13, p. 887 (1995). | | | | | | |
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| pt | 6,231,777 | 05/15/2001 | Kofuji et al. | 216 | 71 | 10/26/1995 |
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| | | | | | | <input type="checkbox"/> YES <input type="checkbox"/> NO |
| OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.) | | | | | | |
| pt | J.T. Verdeyen et al., "Modulated discharges: effect on plasma parameters and deposition," J. Vac. Sci. Technol. A8, p. 1851 (1990). | | | | | |
| EXAMINER P. Hassan zadet | | | | | | |
| DATE CONSIDERED 5-25-03 | | | | | | |

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.